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	Application No.	Applicant(s)	
Notice of Allowability	10/623,680	FUJITA ET AL.	
	Examiner	Art Unit	
	John S. Chu	1752	
The MAILING DATE of this communication ap All claims being allowable, PROSECUTION ON THE MERITS I herewith (or previously mailed), a Notice of Allowance (PTOL-8 NOTICE OF ALLOWABILITY IS NOT A GRANT OF PATENT of the Office or upon petition by the applicant. See 37 CFR 1.3	S (OR REMAINS) CLOSED i 5) or other appropriate comm <b>RIGHTS</b> . This application is	n this application. If not include unication will be mailed in due	ed course. <b>THIS</b>
1. $\square$ This communication is responsive to $4/8/04$ .			
2. ⊠ The allowed claim(s) is/are <u>1-12</u> .			
3.   The drawings filed on are accepted by the Examin	ner.		
4. Acknowledgment is made of a claim for foreign priority  a) All b) Some* c) None of the:  1. Certified copies of the priority documents hat 2. Certified copies of the priority documents hat 3. Copies of the certified copies of the priority of International Bureau (PCT Rule 17.2(a)).  * Certified copies not received:  Applicant has THREE MONTHS FROM THE "MAILING DATE noted below. Failure to timely comply will result in ABANDON THIS THREE-MONTH PERIOD IS NOT EXTENDABLE.  5. A SUBSTITUTE OATH OR DECLARATION must be sub INFORMAL PATENT APPLICATION (PTO-152) which get including changes required by the Notice of Draftspet 1) hereto or 2) to Paper No./Mail Date  [b) including changes required by the attached Examine Paper No./Mail Date  Identifying indicia such as the application number (see 37 CFF each sheet. Replacement sheet(s) should be labeled as such in the department of the paper No./Mail Date  DEPOSIT OF and/or INFORMATION about the department of the paper No./Mail Paper No./Mail Paper No./Mail Date	eve been received.  Eve been received in Application documents have been received.  Every of this communication to fill the NMENT of this application.  Every of this communication to fill the NMENT of this application.  Every of this communication to fill the NMENT of this application.  Every of this communication to fill the NMENT of this application.  Every of this communication to fill the NMENT of this application.  Every of this communication to fill the NMENT of this application.  Every of this communication to fill the NMENT of this application.  Every of this communication to fill the NMENT of this application.  Every of this communication to fill the NMENT of this application.	on No ed in this national stage applicated in this national stage applicated are provided in the national stage applicated are provided in the Office action of the drawings in the front (not the FR 1.121(d).	quirements
Attachment(s)  1. ☑ Notice of References Cited (PTO-892)  2. ☐ Notice of Draftperson's Patent Drawing Review (PTO-948)  3. ☐ Information Disclosure Statements (PTO-1449 or PTO/SE Paper No./Mail Date  4. ☐ Examiner's Comment Regarding Requirement for Deposi of Biological Material	6. Interview S Paper No 3/08), 7. Examiner's	nformal Patent Application (PTo Summary (PTO-413), ./Mail Date s Amendment/Comment s Statement of Reasons for Allo	·
		John S. Chu Primary Examiner Art Unit: 1752	

U.S. Patent and Trademark Office PTOL-37 (Rev. 1-04) Art Unit: 1752

## REASONS FOR ALLOWANCE

1. The following is an examiner's statement of reasons for allowance: The claimed invention is drawn to the following:

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- 1. (Original) A photosensitive resin precursor composition comprising:
- (a) a heat resistant resin precursor polymer;
- (b) a radiation sensitive compound; and
- (c) a solvent expressed by formula (1):

wherein  $R^1$  represents an alkyl group having a carbon number in the range of 1 to 3,  $R^2$ ,  $R^3$ ,  $R^4$ , and  $R^5$  are each selected from among hydrogen and alkyl groups having carbon numbers in the range of 1 to 3, and 1 represents an integer in the range of 0 to 3.

and

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2. (Currently Amended) A photosensitive resin precursor composition according to Claim 1, wherein the solvent is comprising:

(a) a heat resistant resin precursor polymer;

(b) a radiation sensitive compound; and

(c) a solvent expressed by formula (2):

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wherein  $R^6$  to  $R^{10}$  are each selected from among hydrogen and alkyl groups having carbon numbers in the range of 1 to 3, and j and k are each an integer in the range of 0 to 3 and satisfy the relationship  $j + k \ge 2$ .

The inventive step is the use of the solvent as expressed by the formulae (1) or (2). The closest prior art recently located include the disclosure to OKANUMA et al. The reference discloses suitable organic solvents that include diacetone alcohol, which meets the solvent of formula (1). The reference discloses suitable solvents for dissolving the photosensitive materials in Examples 1 and 13. These solvents used in the Examples include N-methyl-pyrrolidone (NMP) and  $\gamma$ -butyrolactone (GBL) which are listed in the specification at column 18, lines 1-18. The skilled artisan is motivated to use any of the listed solvents to dissolve the photosensitive composition, thus making the claimed invention *prima facie* obvious to the skilled artisan to

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reasonably expect same or similar results as disclosed in the Examples when using any of the listed solvents in column 18.

Applicants in their comparative examples include N-methyl-pyrrolidone and γ-butyrolactone and compare it to the claimed solvents. The comparative results demonstrate unexpected results with respect to range (um) in the inventive compositions for instance DAA(diacetone alcohol) demonstrates a lower range of 0.19 to those using NMP or GBL as the solvent, 0.48 and 0.63, respectively.

Because the comparative examples demonstrate unexpected results with respect to range, any rejection under 35 U.S.C. 103 over OKANUMA et al would be overcome for the secondary considerations. Accordingly, claims 1-12 are seen as allowable over the prior art of record and all the claims are passed to issue.

2. Any comments considered necessary by applicant must be submitted no later than the payment of the issue fee and, to avoid processing delays, should preferably accompany the issue fee. Such submissions should be clearly labeled "Comments on Statement of Reasons for Allowance."

Any inquiry concerning this communication or earlier communications from the examiner should be directed to Examiner Chu whose telephone number is (571) 272-1329. The examiner can normally be reached on Monday - Friday from 9:30 am to 6:00 pm.

The fax phone number for the USPTO is (703) 872-9306.

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Any inquiry of a general nature or relating to the status of this application or proceeding should be directed to the Group receptionist whose telephone number is (571) 272-1700.

John S. Chu

Primary Examiner, Group 1700

J.Chu

June 18, 2004